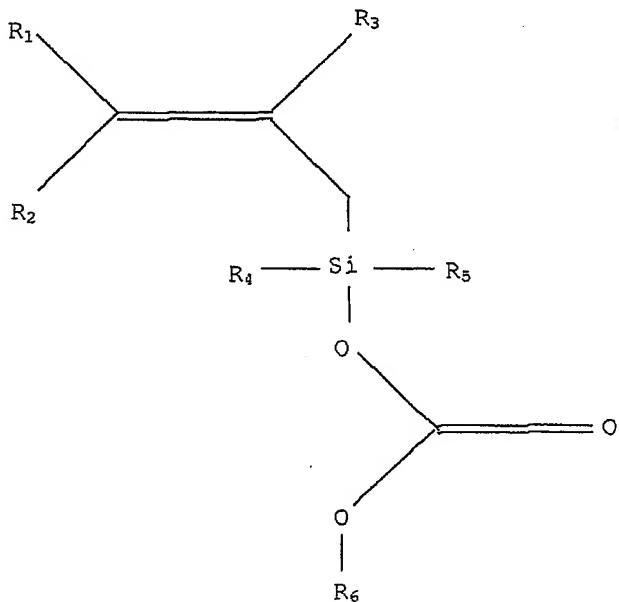


**In the Claims:**

1-13. (Canceled)

14. (Currently Amended) A polymerizable composition for the production of a resist, comprising at least one unsaturated, polymerizable monomer having at least one silicon atom and at least one carbonyl group, a monomer of the general formula:



wherein:

R<sub>1</sub>, is selected from the group consisting of H and alkyl radicals;

R<sub>2</sub>, is selected from the group consisting of H and alkyl radicals;

R<sub>3</sub> is selected from the group consisting of H and alkyl radicals;

R<sub>4</sub> comprises alkyl radicals and/or a silicon-containing compound;

R<sub>5</sub> comprises alkyl radicals and/or a silicon-containing compound;

R<sub>6</sub> comprises alkyl radicals; and

wherein R<sub>1</sub>, R<sub>2</sub>, R<sub>3</sub>, R<sub>4</sub>, R<sub>5</sub>, and R<sub>6</sub> are either identical or different from one another, and

wherein either R<sub>4</sub> or R<sub>5</sub> or both comprise a silicon-containing compound.

15. (Previously Presented) The polymerizable composition as claimed in claim 14 wherein at least one of R<sub>1</sub>, R<sub>2</sub>, R<sub>3</sub> comprises a methyl radical.

16. (Previously Presented) The polymerizable composition as claimed in claim 14 wherein at least one of R<sub>4</sub> and R<sub>5</sub> comprises a methyl radical or siloxane.

17. (Previously Presented) The polymerizable composition as claimed in claim 14 wherein R<sub>6</sub> comprises a tert-butyl radical.

18. (Previously Presented) The polymerizable composition as claimed in claim 14, wherein at least one alkyl radical has a chain length of C<sub>1</sub> to C<sub>8</sub>.

19. (Previously Presented) A polymer prepared by polymerization of at least the composition as claimed in claim 14.

20-33. (Canceled)